

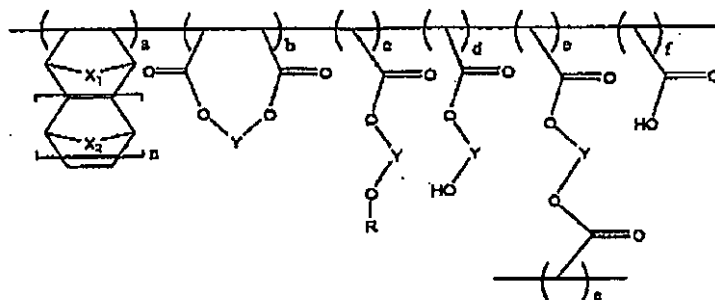
In the Claims:

Please cancel claims 4-7 and 14-21 without prejudice or disclaimer.

Please amend claim 1 as follows:

Claim 1 (currently amended) A photoresist polymer comprising a repeating unit of following formula 1:

Formula 1



wherein, X_1 and X_2 are independently selected from the group consisting of CH_2 , CH_2CH_2 , O and S;

Y is C_1 - C_{10} alkylene or alkylene comprising an ether linkage;

R is an acid labile protecting group;

n is an integer from 0 to 2; and

a : b : c : d : e : f is 20-40mol% : 1- present in an amount up to and including 20mol%: 20-70mol% : 1- present in an amount up to and including 30mol%: 1 present in an amount up to and including 20mol%: 0-20mol%.

Claim 2 (original) The photoresist polymer according to claim 1, wherein the acid labile protecting group is selected from the group consisting of tert-butyl, tetrahydropyran-2-yl, 2-methyl tetrahydropyran-2-yl, tetrahydrofuran-2-yl, 2-methyl tetrahydrofuran-2-yl, 1-methoxypropyl, 1-methoxy-1-methylethyl, 1-ethoxypropyl, 1-ethoxy-1-methylethyl, 1-methoxyethyl, 1-ethoxyethyl, tert-butoxyethyl, 1-isobutoxyethyl and 2-acetylmenth-1-yl.

Claim 3 (original) The photoresist polymer according to claim 1, wherein n is 0, X_1 is CH_2 , Y is CH_2CH_2 or $CH_2CH_2OCH_2CH_2$, and R is tert-butyl.

Claims 4-7 (currently canceled)